PATENT COOPERATION TREATY

NTERNATIONAL SEARCHING AUTH	ORITY			40.6 ×
Го:			PCT	ans lation
			RITTEN OPINION OF T IONAL SEARCHING A	HE
			(PCT Rule 43bis.1)	
		Date of mailing (day/month/year)		
Applicant's or agent's file reference pf-3291		FOR FURTHER	ACTION See paragraph 2 below	
International application No. PCT/JP2004/007791	International filing date 28.05.2004	(day/numh/year)	Priority date (duy/month/yet	ir)
International Patent Classification (IPC) or	both national classification an	nd IPC	•	
Applicant				
NEC CORPORATION				
1. This opinion contains indications relating to the following items: Box No. 1 Basis of the opinion			vitten opinion of th ses an Authority othe at written opinions o submit to the IPEA	
Name and mailing address of the ISA/JP		Authorized officer		
Facsimile No.		Telephone No.		

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Во	nx No. 1 Basis of this optimon
1.	With regard to the language, this opinion has been established on the basis of the international application in the language in which it was filed, unless otherwise indicated under this item.
	This opinion has been established on the basis of a translation from the original language into the following language . which is the language of a translation furnished for the purposes of international search (under
	Rule 12.3 and 23.1(b)).
2.	With regard to any nucleotide and/or amino ocid sequence disclosed in the international application and necessary to the claimed invention, this opinion has been established on the basis of:
	a. type of material
	a sequence listing
	table(s) related to the sequence listing
	b. format of material
	in written format
	in computer readable form
l	c. time of Gling/furnishing
	contained in the international application as filed.
	filed together with the international application in computer readable form.
	furnished subsequently to this Authority for the purposes of search.
3	In addition, in the case that more than one version or copy of a sequence listing and/or table(s) relating thereto has been filed or furnished, the required statements that the information in the subsequent or additional copies is identical to that in the application as filed or does not go beyond the application as filed, as appropriate, were furnished.
4	. Additional comments:
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→→→ Sughrue, Mion

Box	No. IV	Lack of unity of invention				
1.	1. In response to the invitation (Form PCT/ISA/206) to pay additional fees the applicant has:					
	paid additional fees					
	[paid additional fees under protest				
	[not paid additional fees				
2.		This Authority found that the requirement of unity of invention is not complied with additional fees.	and chose not to invite the applicant to pay			
3.	This A	Authority considers that the requirement of unity of invention in accordance with Rules	13.1, 13.2 and 13.3 is			
		complied with				
	\boxtimes	not complied with for the following reasons:				
		Claims 1 to 23 have a common feature of relating of formed on an insulating film located on a substrate, but be known from reference sources, this feature cannot be considerature. Therefore, there is no special technical feature for group described by claims 1 to 23 so as to form a single gothis reason, the inventions of the groups described in claim satisfy the requirement of unity of inventions. Furthermore, the number of groups of inventions ageneral inventive concept that are described in the claims application, that is, the number of inventions are examined. From the special features of the inventions describe can be inferred that four inventions divided into [1-18], [1 described in the claims of the international patent applicat. The invention of claims [1-18] is considered in grefeature described in claim 1 is described in [JP 2000-1831 Electric Co., Ltd.)], it cannot serve as a special technical form a single general inventive concept. Therefore describe four inventions divided into [1, 2], [3-9, 13-15, 1]. Furthermore, the examination of the inventions de 12], [16] demonstrates that those inventions are linked in insulating barrier layer comprising silicon and an organic Furthermore, the examination of the inventions de 23], [22] demonstrates that those inventions are linked in structure of multilayer wiring and a method for manufacture of multilayer wiring and a method for manufacture for this examination finds that a total of the 16, 21-23], [3-9, 13-15, 17, 18], [19, 20] are described in	cause this feature is well sidered as a special technical linking the inventions of a eneral inventive concept. For ms 1 to 23 obviously do not so linked as to form a single of the international patent d below. Seed in independent claims, it 19, 20], [21, 23], [22] are tion. Seater detail below. Because the 166 A, Full text (Nippon feature linking the inventions see, claims [1-18] apparently [7, 18], [10-12], and [16]. Secribed in claims [1, 2], [10-terms of relating to an compound. Secribed in claims [1, 2], [21, terms of relating a wiring ure thereof. The secribed in compound of [1, 2, 10-12].			
	_	patent application.	national application			
4.	Cons	sequently, this opinion has been established in respect of the following parts of the inter-	нацоваї аррисанов:			
		all parts				
		the parts relating to claims Nos.				

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Bo			de 43bis.1(akl) with regard to novelty, inventive step or industrial applicability; oporting such statement	
l.	Statement			
	Novelty (N)	Claims	5-20, 22, 23	YES
		Claims	1-4, 21	NO
	Inventive step (IS)	Claims		YES
		Claims	1-23	NO
	Industrial applicability (IA)	Claims	1-23	YES
		Claims		NO
2.	Citations and explanations:	<u> </u>		
	Document 2: WO 2002 drawings	/058134 1	(NEC Corp.), 30 June 2000, Full text, all drawings A1 (STMICROELECTRONICS SA), 25 July 2002, Full text, a	
	Document 3: WO 2001 drawings	/054190	AI (ADVANCED MICRO DEVICES), 26 July 2001. Full text	, all
	Document 4: TADA M epi-contac	cts buried	nrier-metal-free (BMF), Cu dual-damascene interconnects with in anti-diffusive, low-k organic film, 2001 Symposium on VL ne 2001, pp. 13-14	

Claims 1 to 3

The inventions of claims 1 to 3 do not appear to possess novelty or involve an inventive step based on document 1, document 2, and document 3.

Document 5: JP 2002-83870'A (Tokyo Electron, Ltd.), 22 March 2002, Full text, all drawings

Claim 4

The invention of claim 4 does not appear to possess novelty or involve an inventive step based on document 2. In the invention described in document 2, the films corresponding to the first insulating film and second insulating film of the invention of the present application are inorganic films. Therefore, the content of carbon in the insulating barrier film comprising an organic substance is apparently higher than that of the first and second insulating films.

Furthermore, the invention described in claim 4 does appear to involve an inventive step based on document 3. In the invention described in document 3, forming the film corresponding to the first insulating film from an inorganic film would be easy for a person skilled in the art.

Claims 5, 6, 17, 18

The inventions of claims 5 and 6 do not appear to involve an inventive step based on document 2 and document 3. Forming the film corresponding to the second insulating film in the invention described in document 2 and forming the film assumable as the first insulating film and second insulating film in the invention described in claim 3 as inorganic films could be easily conceived of by a person skilled in the art.

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l. Certa	in published documents (Rule 43bis.) a	nd 70.10)		
	Application No. Patent No.	Publication date (day/month/year)	Filing date (day/month/veur)	Priority date (valid claim (dov/month/war)
	2004-200203 A	15.07.2004	16.12.2002	
	2004-193326 A/	08.07.2004	11.12.2002	
	2003-347403 A / [EX]	05.12.2003	30.05.2002	

2. Non-written disclosures (Rule 43bis.1, and 70.9)

Kind of non-written disclosure

Date of non-written disclosure (day/month/year)

Date of written disclosure referring to non-written disclosure (day/month/year)

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WRITTEN OPINION OF THE

International application No.

→→→ Sughrue, Mion

	INTERNATIONAL SEARCHING AUTHORITY	PCT/JP2004/007791
Box No. VIII C	Certain observations on the international application	
The following observe the description, are n	vations on the clarity of the claims, description, and drawings or on the nade:	e question whether the claims are fully supported by
	utual arrangement of "the third insulating film",	"fourth insulating film", and "via
interlayer	insulating film" in claims 5 and 9 is not clear.	
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•		

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Supplemental Box

In case the space in any of the preceding boxes is not sufficient. Continuation of V.2:

As for claims 17, 18, making the films corresponding to the first and second insulating films from the same material and specifically limiting this material to SiCN or the like could be easily conceived of by a person skilled in the art.

Claims 7, 8, 10, 11, 16

The inventions of claims 7, 8, 10, 11, 16 do not appear to involve an inventive step based on document 2 and document 3. Insulating films comprising Si-O bonds are well known as insulating films comprising an organic compound. Furthermore, the content of silicon atoms can be appropriately set by a person skilled in the art.

Claim 9

The invention of claim 9 does not appear to involve an inventive step based on document 2 and document 3. Making the films corresponding to the third insulating film and fourth insulating film from the same material in the inventions described in document 2 and document 3 could be easily conceived of by a person skilled in the art.

Claims 12-15

The invention described in document 12 does not appear to involve an inventive step based on document 2, document 3, and document 4. Document 4 discloses that divinylcyclohexane benzocyclobutene has a barrier property against the diffusion of Cu. Therefore, employing the technology described in document 4 as a barrier insulating film with the object of preventing the diffusion of copper in the inventions described in document 2 and document 3 could be easily conceived of by a person skilled in the art. Furthermore, with respect to the inventions described in claims 13-15, the material for an interlayer insulating film or an etching stopper film can be appropriately selected from well-known materials and limiting the range of materials as described in claims 3-15 could have easily been conceived of by a person skilled in the art.

Claims 19, 20

The inventions of claims 19 and 20 do not appear to involve an inventive step based on document 5. Using a porous interlayer insulating film with the object of reducing the dielectric constant of the interlayer insulating film in the invention described in document 5 could have easily been conceived of by a person skilled in the art.

Claim 21

The invention described in claim 21 does not appear to possess novelty or involve an inventive step based on document 2.

Claim 22

The invention described in claim 22 does not appear to involve an inventive step based on document 2. Forming a film corresponding to the second insulating film in the invention described in document 2 could be easily conceived of by a person skilled in the art.

Claim 23

The invention described in claim 23 does not appear to involve an inventive step based on document 2 and document 4. Using a plasma polymerization method disclosed in document 4 as a method for forming a barrier insulating film could be easily conceived of by a person skilled in the art